

Supporting Information for “Enhanced Urea Oxidation Catalysis through Ni Single-Atom Doping on Cu₂O Surfaces: A Computational Study”

Xiaoqing Li,^a Haiping Lin,^b Wenjing Huang,^{a,*} Shiyun Xiong,^{a,*} Shaoming Huang^{a,*}

^a School of Materials and Energy, Guangdong University of Technology, Guangzhou 510006, Guangdong, China. E-mail: wjhuang42@gdut.edu.cn; syxiong@gdut.edu.cn; smhuang@gdut.edu.cn.

^b School of Physics and Information Technology, Shaanxi Normal University, Xian 710119, Shaanxi, China.

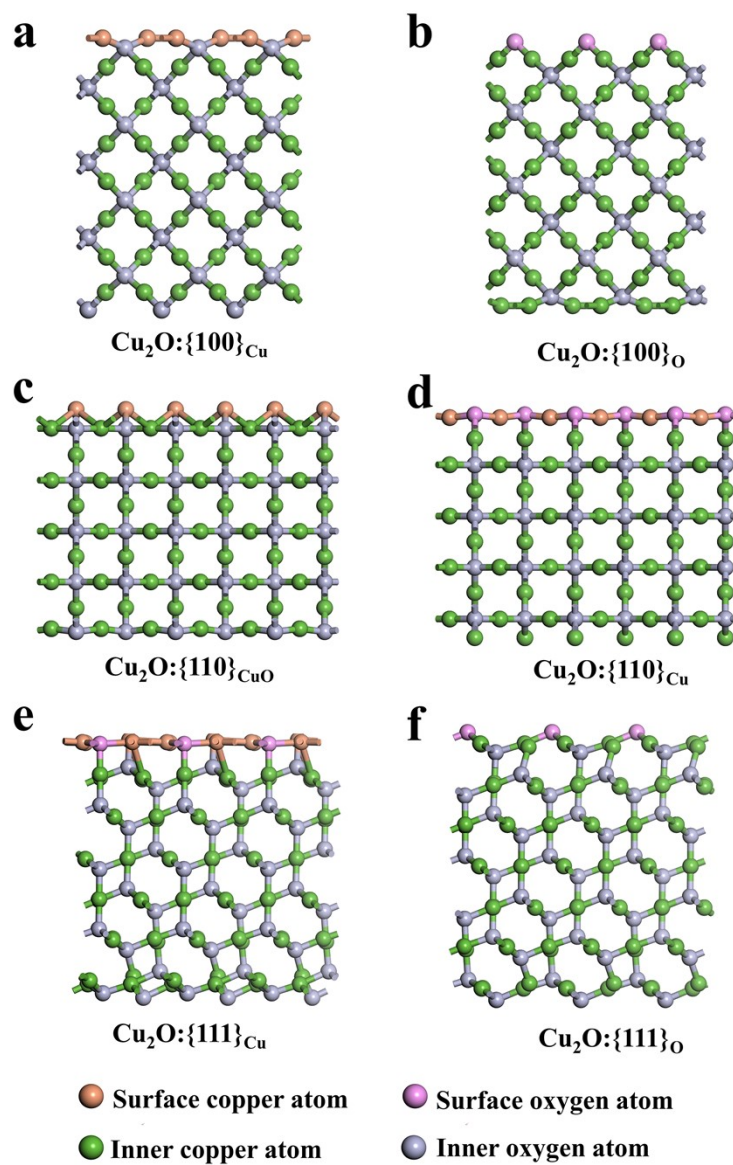


Fig. S1 Side view of the six low-index surfaces of Cu_2O after relaxation. In the $\text{Cu}_2\text{O}:\{111\}_{\text{Cu}}$ structure, the surface Cu atoms are relaxed to the same atomic plane as the subsurface O atoms.

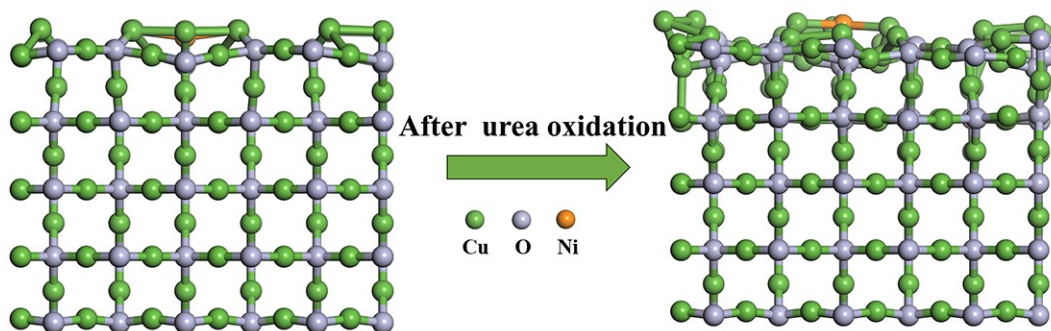
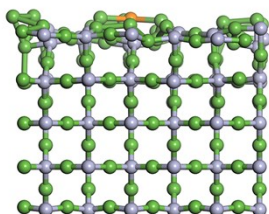


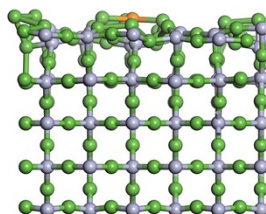
Fig. S2 Surface reconstruction of $\text{Ni-Cu}_2\text{O}:\{110\}_{\text{Cu}}$ during urea adsorption process. Left: before urea adsorption; Right: after urea adsorption.

$\text{Ni-Cu}_2\text{O}:\{110\}_{\text{Cu}}$

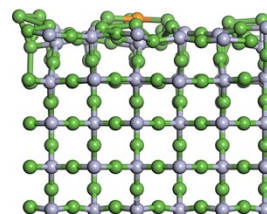
0 eV/Å



0.03 eV/Å

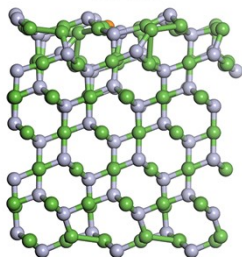


0.3 eV/Å

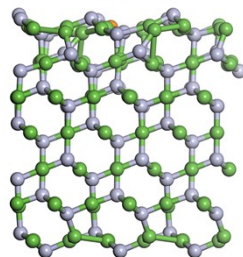


$\text{Ni-Cu}_2\text{O}:\{111\}_{\text{O}}$

0 eV/Å



0.03 eV/Å



0.3 eV/Å

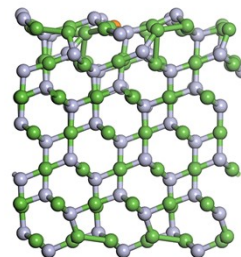


Fig. S3 The optimized structures for $\text{Ni-Cu}_2\text{O}:\{110\}_{\text{Cu}}$ and $\text{Ni-Cu}_2\text{O}:\{111\}_{\text{O}}$ under different electric fields.

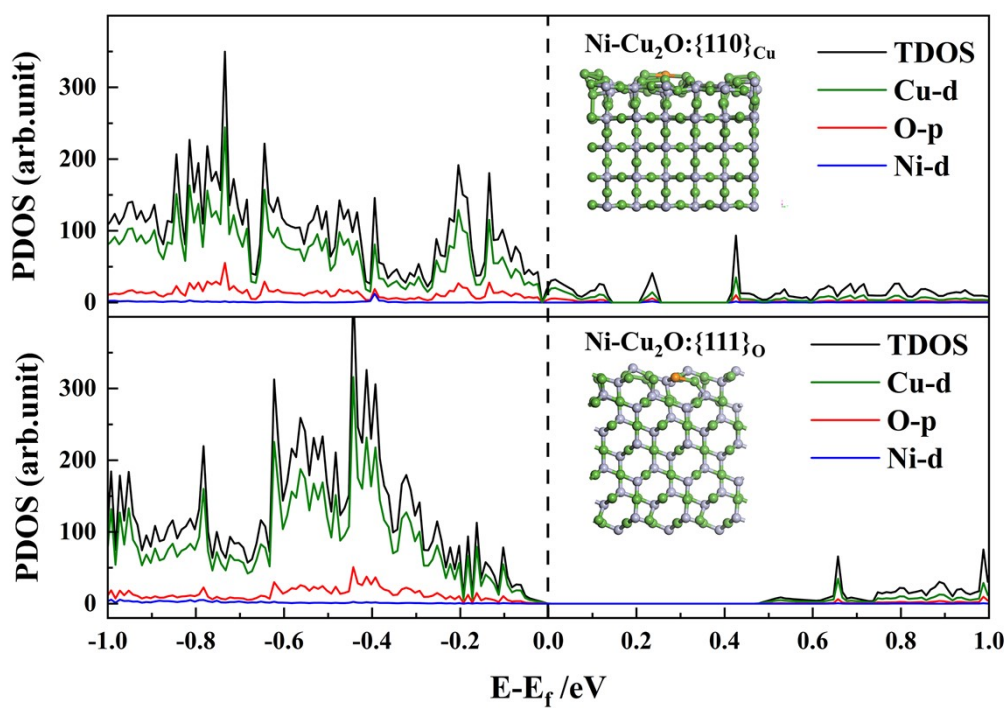


Fig. S4 TDOS and PDOS of Cu-d, Ni-d, and O-p orbitals in $\text{Ni-Cu}_2\text{O}:\{110\}_{\text{Cu}}$ (top) and $\text{Ni-Cu}_2\text{O}:\{111\}_{\text{O}}$ (bottom). Orange, green, and silver colors denote Ni, Cu, and O atoms, respectively.

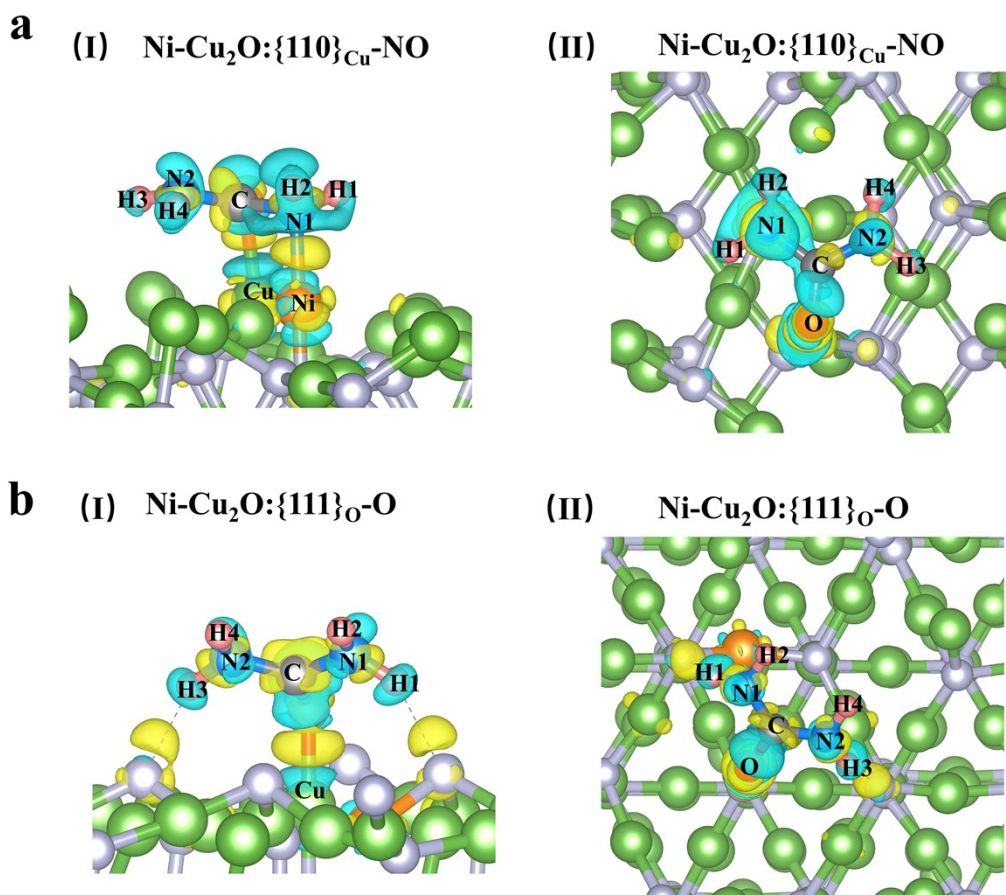


Fig. S5 Differential charge density maps for $\text{Ni-Cu}_2\text{O}:\{110\}_{\text{Cu}}\text{-NO}$ (a) and $\text{Ni-Cu}_2\text{O}:\{111\}_{\text{O}}\text{-O}$ (b). The side and top views are illustrated in (I) and (II) of the corresponding subfigure. In all plots, the isosurface is set to $0.003 \text{ e}\text{\AA}^{-3}$.

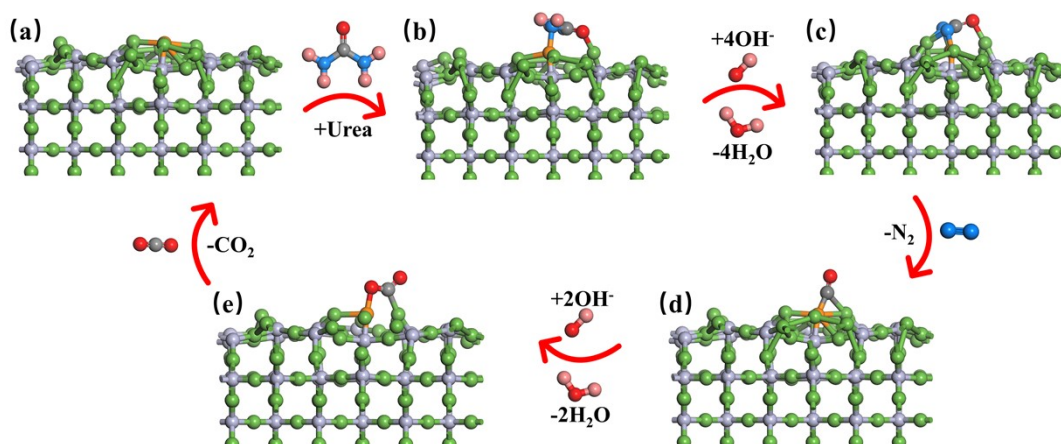
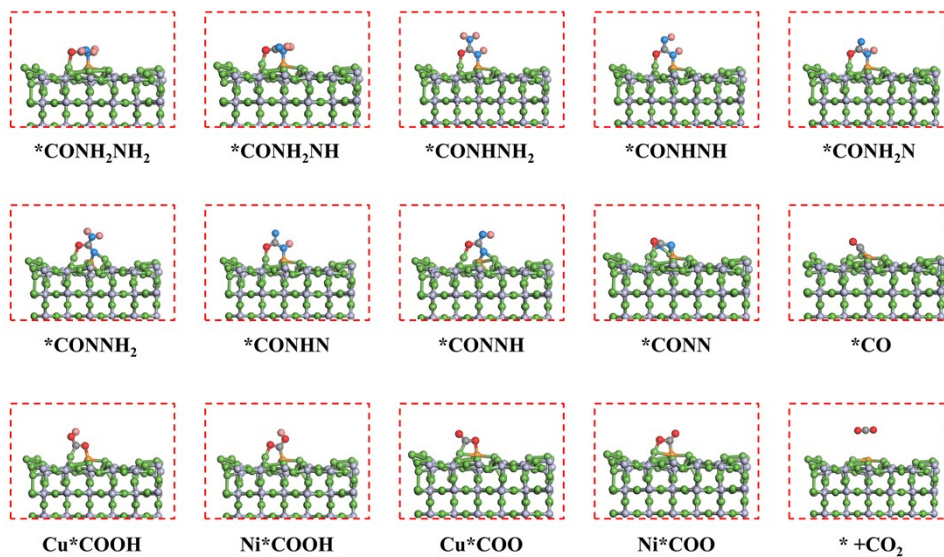


Fig. S6 Schematic diagram of the reaction path flow for the oxidation of urea to N_2 and CO_2 .

a Ni-Cu₂O:{110}_{Cu}



b Ni-Cu₂O:{111}_O

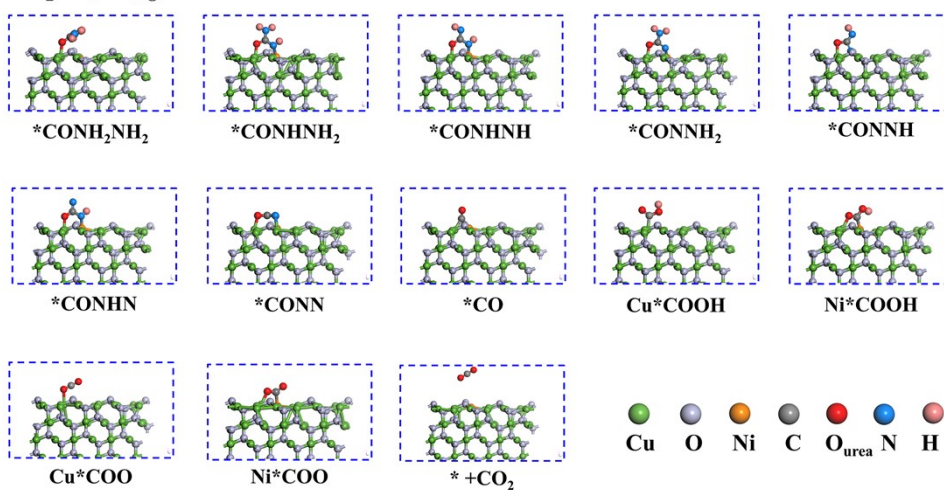


Fig. S7 Optimized atomic structures of various intermediates during UOR reaction for (a) Ni-Cu₂O:{110}_{Cu}-NO and (b) Ni-Cu₂O:{111}_O-O.

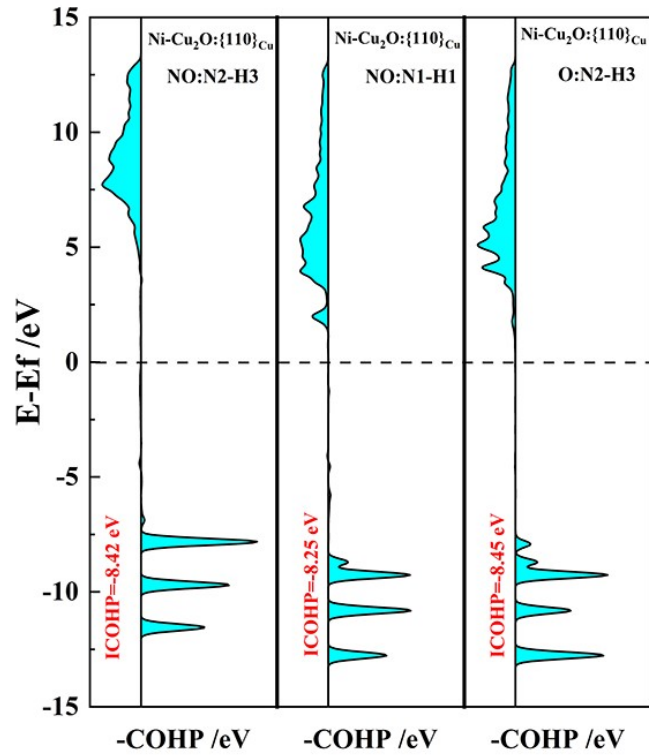


Fig. S8 Variation of -COHP with energy for the N-H bonds in Ni-Cu₂O:{110}_{Cu}-NO and Ni-Cu₂O:{111}_O-O.

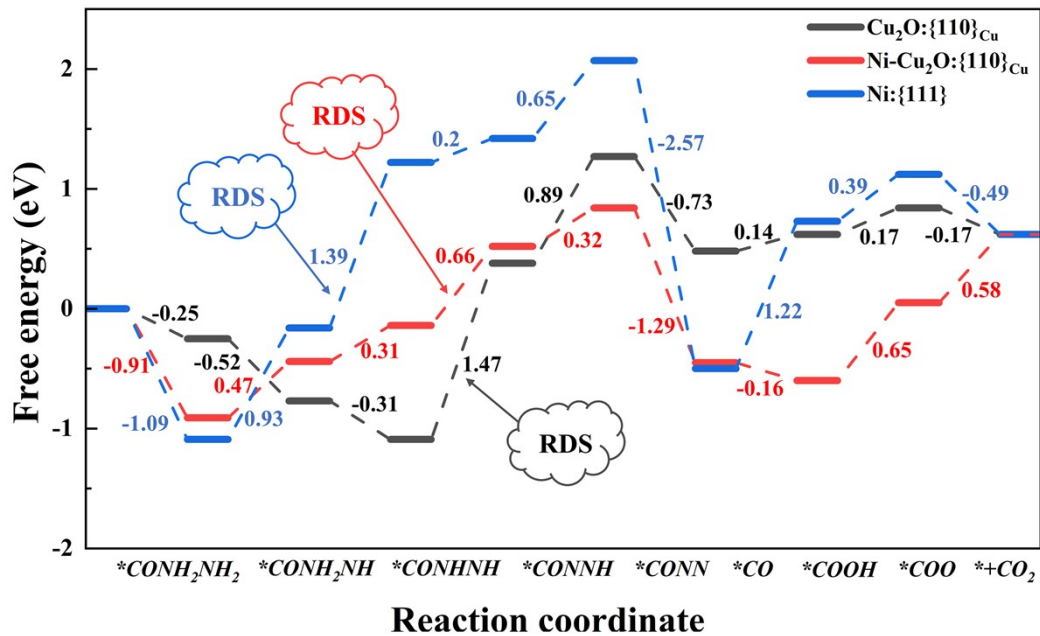
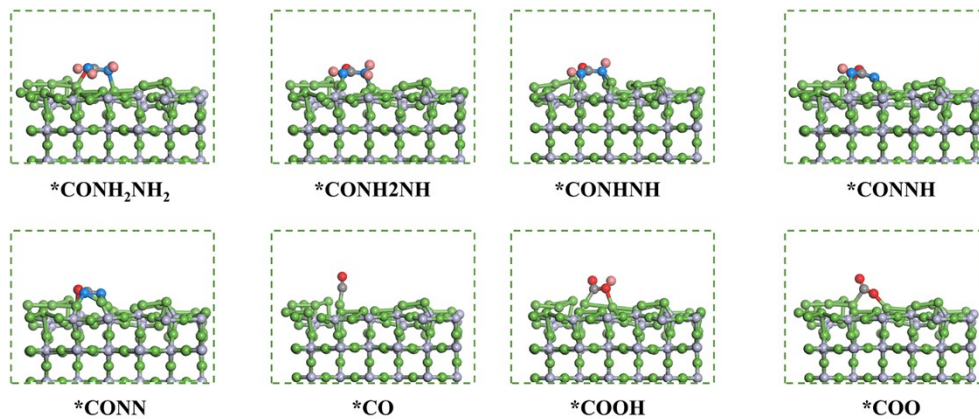


Fig. S9 Gibbs free energies of each intermediate during UOR on Ni:{111}, Cu₂O:{110}_{Cu}, and Ni-Cu₂O:{110}_{Cu}.

a $\text{Cu}_2\text{O}:\{110\}_{\text{Cu}}$



b $\text{Ni}:\{111\}$

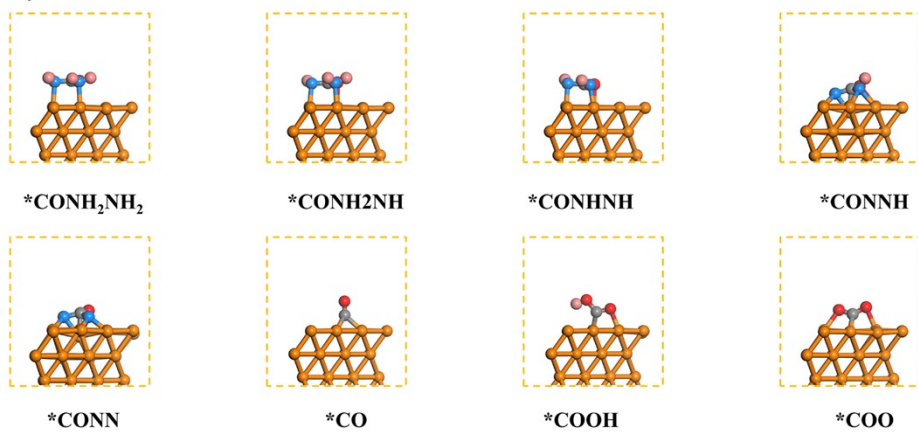


Fig. S10 Optimized atomic structures of various intermediates during UOR reaction for (a) $\text{Cu}_2\text{O}:\{110\}_{\text{Cu}}$ and (b) $\text{Ni}:\{111\}$.

Table S1. Gibbs free energies, zero-point energies, and entropies of the reaction intermediates in Ni-Cu₂O:{111}_O and Ni-Cu₂O:{110}_{Cu} catalysts.

Species	ZPE (eV)		TS (eV)	
	Ni-Cu ₂ O:{110} _{Cu}	Ni-Cu ₂ O:{110} _{Cu}	Ni-Cu ₂ O:{111} _O	Ni-Cu ₂ O:{111} _O
*CONH ₂ NH ₂	1.75	0.28	1.74	0.31
*CONH ₂ NH	1.42	0.25	\	\
*CONH ₂ NH ₂	1.43	0.25	1.14	0.26
*CONH ₂ NH	1.06	0.25	1.06	0.25
*CONH ₂ N	1.06	0.26	\	\
*CONNH ₂	1.10	0.23	1.09	0.23
*CONHN	0.74	0.23	0.72	0.24
*CONNH	0.75	0.21	0.72	0.24
*CONN	0.46	0.13	0.44	0.17
*CO	0.20	0.10	0.2	0.15
Cu*COOH	0.64	0.17	0.61	0.22
Ni*COOH	0.64	0.18	0.56	0.18
Cu*COO	0.31	0.18	0.32	0.19
Ni*COO	0.31	0.16	0.32	0.19

Table S2. The d-band center ϵ_d of the active sites before and after urea molecules adsorption. For urea molecules adsorbed by dual active sites, we adopt the method in Ref [1].

Catalyst	ϵ_d (eV) before adsorption	ϵ_d (eV) after adsorption
Ni-Cu ₂ O:{110} _{Cu}	-1.47	-1.77
Ni-Cu ₂ O:{111} _O	-1.21	-1.02

Table S3. Comparison of urea adsorption energy, overpotential, and CO₂ desorption energy in various UOR electrocatalysts reported in literatures. The UOR mechanisms in literatures include both conventional adsorption mechanisms and lattice oxygen mechanisms (LOM). The ΔG_{\max} of dehydrogenation represents the maximum dehydrogenation reaction energy.

Catalyst	ΔG_{\max} of dehydrogenation (eV)	CO ₂ desorption energy (eV)	Overpotential (V)	Ref.
Ni-Cu₂O:{110}_{Cu}	0.66	0.58	0.29	This work
NiOOH	1.44	0.9	1.07	[2]
NiOO (LOM)	0.96	0.4	0.59	[2]
LNO-2	0.69	1.05	0.68	[3]
LNO-2 (LOM)	0.69	0.11	0.32	[3]
CoNi@CN-CoNiMoO	1.15	-0.32	0.78	[4]
O _{vac} -V-Ni(OH) ₂	2.35	0.67	1.98	[5]
Ac-CoOCl-V	2.05	-0.74	1.68	[6]
Ru-Co DAS/NiO	1.63	0.56	1.26	[7]

Table S4. Calculated d-band centers for *COO intermediate. For Ni-Cu₂O:{111}_O-Cu*COO, CO₂ is adsorbed solely by a Cu atom, while for other structures, CO₂ is adsorbed by multiple active sites.

Species	ϵ_d (eV)
Ni-Cu ₂ O:{110} _{Cu} -Ni*COO	-1.41
Ni-Cu ₂ O:{110} _{Cu} -Cu*COO	-1.82
Ni-Cu ₂ O:{111} _O -Ni *COO	-1.53
Ni-Cu ₂ O:{111} _O -Cu*COO	-1.67

Table S5. Gibbs free energies, zero-point energies, and entropies of the reaction intermediates for Ni:{111} and Cu₂O:{110}_{Cu} catalysts.

Species	ZPE (eV)	TS (eV)	ZPE (eV)	TS (eV)
	Ni:{111}	Ni:{111}	Cu ₂ O:{110} _{Cu}	Cu ₂ O:{110} _{Cu}
*CONH ₂ NH ₂	1.71	0.2	1.73	0.30
*CONH ₂ NH	1.40	0.25	1.45	0.21
*CONH ₂ NH	1.07	0.20	1.16	0.25
*CONNH	0.72	0.17	0.78	0.16
*CONN	0.43	0.14	0.46	0.14
*CO	0.19	0.14	0.19	0.18
*COOH	0.59	0.16	0.59	0.16
*COO	0.28	0.18	0.29	0.23

References:

- 1 S. Ponath, M. Menger, L. Grothues, M. Weber, D. Lentz, C. Strohmann and M. Christmann, *Angew. Chem. Int. Ed.*, 2023, **62**, e202216920.
- 2 L. Zhang, L. Wang, H. Lin, Y. Liu, J. Ye, Y. Wen, A. Chen, L. Wang, F. Ni, Z. Zhou, S. Sun, Y. Li, B. Zhang and H. Peng, *Angew. Chem. Int. Ed.*, 2019, **58**, 16820-16825.
- 3 W.-K. Han, J.-X. Wei, K. Xiao, T. Ouyang, X. Peng, S. Zhao and Z.-Q. Liu, *Angew. Chem. Int. Ed.*, 2022, **61**, e202206050.
- 4 G. Qian, J. Chen, W. Jiang, T. Yu, K. Tan and S. Yin, *Carbon Energy*, 2023, **5**, e368.
- 5 H. Qin, Y. Ye, J. Li, W. Jia, S. Zheng, X. Cao, G. Lin and L. Jiao, *Adv. Funct. Mater.*, 2023, **33**, 2209698.
- 6 B. Zhang, C. Pan, H. Liu, X. Wu, H. Jiang, L. Yang, Z. Qi, G. Li, L. Shan, Y. Lin, L. Song and Y. Jiang, *Chem. Eng. J.*, 2022, **439**, 135768.
- 7 X. Zheng, J. Yang, P. Li, Z. Jiang, P. Zhu, Q. Wang, J. Wu, E. Zhang, W. Sun, S. Dou, D. Wang and Y. Li, *Angew. Chem. Int. Ed.*, 2023, **62**, e202217449.